

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: H. MIURA et al.
Serial No.: Rule 1.53(b) Continuation of U.S. Patent Application
Serial No. 09/893,980 filed June 29, 2001
Filed: July 25, 2003
For: SEMICONDUCTOR MEMORY DEVICE
Art Group of Parent: 2818
Examiner of Parent: Long K. Tran

**INFORMATION DISCLOSURE STATEMENT
UNDER 37 C.F.R. §1.97 AND §1.98**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

July 25, 2003

Sir:

This Information Disclosure Statement is being filed in accordance with 37 C.F.R. §1.97 along with a Form PTO-1449. This Information Disclosure Statement is being filed simultaneously with the filing of this application.

This application claims priority under 35 U.S.C. §120 from parent Application Nos. 09/893,980, filed June 29, 2001, 08/838,259, filed April 17, 1997, and 08/270,472, filed July 5, 1994. Thus, in accordance with 37 C.F.R. §1.98(d), copies of the references cited or submitted in the parent applications do not need to be filed by the applicant.

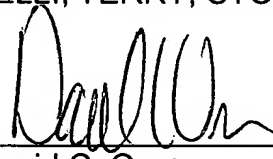
It is respectfully requested that this Information Disclosure Statement be considered by the Examiner.

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to the deposit account of Antonelli, Terry, Stout & Kraus, Deposit Account No. 01-2135 (500.33045CC3) and please credit any excess fees to such Deposit Account.

Respectfully submitted,

ANTONELLI, TERRY, STOUT & KRAUS, LLP

By

A handwritten signature in black ink, appearing to read "David C. Oren", written over a horizontal line.

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Substitute for form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		Complete if Known	
		Application Number	
		Filing Date	July 25, 2003
		First Named Inventor	MIURA et al.
		Art Unit	Unassigned
Examiner Name	Unassigned		
Sheet 1 of 1	Attorney Docket Number	500.33045CC3	

U.S. PATENT DOCUMENTS						
Examiner Initials ¹	Cite No. ¹	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)				
		US-4,839,306		06/1989	Wakamatsu	
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Examiner Initials ²	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Country	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ -Number ⁴ -Kind Code ⁵ (if known)				
		JP 3-96249	04/1991	Japan (Abstract only)		
		JP 3-236283	10/1991	Japan		
		JP 4-127433	04/1992	Japan (Abstract only)		

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Chiu et al., "A Bird's Beak Free Local Oxidation Technology Feasible for VLSI Circuits Fabrication", IEEE TRANSACTIONS ON ELECTRON DEVICES, Vo. ED-29, No. 4, 1983, pages 536-540	

Examiner Signature	Date Considered
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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